

Claims:

1. An apparatus for treating a workpiece with plasma, comprising:
 - a vacuum chamber having a chamber base and a chamber lid movable relative to
 - 5 said chamber base between a closed position that defines a processing space and an
 - open position for transferring a workpiece having an exposed surface into and out of
 - said processing space;
 - an exhaust port in said vacuum chamber for evacuating said processing space;
 - a workpiece holder located in said processing space and comprising a
 - 10 substantially planar support platform;
 - a process gas supply port in said vacuum chamber for introducing a process gas
 - to said processing space; and
 - a plasma excitation source operable to provide a plasma in said processing space
 - from the process gas and including an RF power supply and a powered electrode which
 - 15 is substantially parallel to the planar support platform of the workpiece holder and
 - electrically connected to said RF power supply; and
 - wherein said chamber lid includes a sidewall section capable of being removed
 - from or added to said chamber lid for changing a vertical dimension of said vacuum
 - chamber by changing the dimension of ~~said~~ said chamber lid in the vertical direction so
 - 20 as to maintain a reproducible distance between said powered electrode and the exposed
 - surface of the workpiece.